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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/809,906	03/26/2004	Rahul Surana	008089 USA/MTCG/PCTRL	7260
7590	10/05/2006		EXAMINER	
Applied Materials, Inc. P.O. Box 450A Santa Clara, CA 95052			MCDONALD, SHANSESE L	
			ART UNIT	PAPER NUMBER
			3723	

DATE MAILED: 10/05/2006

Please find below and/or attached an Office communication concerning this application or proceeding.

Office Action Summary	Application No.	Applicant(s)
	10/809,906	SURANA ET AL.
	Examiner Shantese L. McDonald	Art Unit 3723

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) OR THIRTY (30) DAYS, WHICHEVER IS LONGER, FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) Responsive to communication(s) filed on 13 July 2006.
 2a) This action is FINAL. 2b) This action is non-final.
 3) Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) Claim(s) 1-44 is/are pending in the application.
 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
 5) Claim(s) _____ is/are allowed.
 6) Claim(s) 1-44 is/are rejected.
 7) Claim(s) _____ is/are objected to.
 8) Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) The specification is objected to by the Examiner.
 10) The drawing(s) filed on _____ is/are: a) accepted or b) objected to by the Examiner.
 Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
 Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
 a) All b) Some * c) None of:
 1. Certified copies of the priority documents have been received.
 2. Certified copies of the priority documents have been received in Application No. _____.
 3. Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|--|---|
| 1) <input type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413) |
| 2) <input checked="" type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | Paper No(s)/Mail Date. _____ |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO/SB/08)
Paper No(s)/Mail Date _____ | 5) <input type="checkbox"/> Notice of Informal Patent Application |
| | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless –

(e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.

Claims 1-44 are rejected under 35 U.S.C. 102(e) as being anticipated by

Redeker et al.

Redeker et al. teaches a method for qualifying a semiconductor manufacturing tool, by using a computer readable medium, 90, comprising transferring a single patterned wafer to a bulk removal polishing platen, (col. 7, lines 31-63), measuring in situ bulk removal polishing platen characteristics, which include polishing rate, nonuniformity and defectivity, from the wafer during the processing by the bulk removal polishing platen, using an eddy current measuring sensor implemented at the bulk removal polishing platen; (col. 9, lines 57-59), qualifying the bulk removal polishing platen by adjusting one or more parameters of a recipe in accordance with the one or more bulk removal polishing platen characteristics, (col. 10, lines 46-61). Redeker et al. also teaches transferring the wafer to a copper clearing platen, measuring in situ, using a laser interferometer, (col. 8, lines 57-65 and col. 11, lines 19-20), copper clearing platen qualification characteristics from the wafer during processing by the copper

clearing platen, and qualify the copper clearing platen by adjusting one or more parameters of the recipe, (col. 10, line 62-col. 11, line 54), and transferring a wafer to a barrier removal polishing platen, measuring in situ, using an optical sensor, (col. 11, lines 64-65), barrier removal platen qualification characteristics and qualifying the barrier removal polishing platen by adjusting one or more parameters of the recipe, (col. 11, lines 55-67). Redeker also teaches measuring in situ a defectivity from the wafer and qualifying the tool for the defectivity by adjusting one or more parameters of the recipe, (col. 10, lines 13-34), and using the recipe in the processing of one or more subsequent wafers by at least each of the bulk removal polishing platen, the copper clearing platen and the barrier removal polishing platen, (col.2, lines 26-43 of 09/609,426 which is US 6,776,692 which was incorporated by reference as stated in col. 10, line 24 of Redeker).

Response to Arguments

Applicant's arguments filed 7/13/06 have been fully considered but they are not persuasive.

The Applicant argues that Redeker fails to teach one or more parameter of a recipe. The Examiner has noted that Redeker incorporates by reference, in col. 10, line 24, case US 6,776,692, which does indeed teach a polishing recipe in col. 2, lines 26-43.

Conclusion

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shantese L. McDonald whose telephone number is (571) 272-4486. The examiner can normally be reached on 8:00 a.m. - 4:30 p.m..

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Joseph Hail can be reached on (571) 272-4485. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free). If you would like assistance from a USPTO Customer Service Representative or access to the automated information system, call 800-786-9199 (IN USA OR CANADA) or 571-272-1000.

S.L.M.
September 19, 2006


Joseph J. Hail, III
Supervisory Patent Examiner
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